

Amended

at least one-stage step portions formed between said polishing faces of said polishing projections and the bottoms of said polishing agent passages, wherein:
said polishing cloth has a flat plate portion;
said polishing projections are formed as projecting from said flat plate portion;
said polishing agent passages are formed by grooves formed in said flat plate portion; and
the surface of said flat plate portion forms said step portions.

6 5. (Once Amended) A chemical mechanical polishing apparatus comprising:
a chemical mechanical polishing cloth for chemically mechanically polishing a workpiece;

a polishing head for holding and rubbing a workpiece with said chemical mechanical polishing cloth; and

9 a polishing agent supply mechanism for supplying a polishing agent to said chemical mechanical polishing cloth,

said mechanical polishing cloth including, on an opposite-to-workpiece face thereof:

polishing projections having polishing faces arranged to come in contact with a workpiece for polishing same;

polishing agent passages, having bottoms, for introducing a polishing agent; and
at least one-stage step portions formed between said polishing faces of said polishing projections and the bottoms of said polishing agent passages, wherein
said polishing cloth has a flat plate portion;
said polishing projections are formed as projecting from said flat plate portion;